S/N 08/903,486

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Leonard Forbes et

Serial No.:

08/903,486

Filed: Title:

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ANSISTOR SILICON CARBIDE

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Examiner: W. Mintel

Group Art Unit: 2811

Docket: 303.326US1

AMENDMENT AND RESPONSE

Box RCE Commissioner for Patents Washington, D.C. 20231

The applicant has reviewed the Office Action mailed June 6, 2000. Please amend the application as follows:

## IN THE CLAIMS

Please cancel claims 6, 7, 23, 30, 36, 49 and 54 and amend the claims as follows:

[Twice Amended] A transistor comprising: 1.

a source region, a drain region, and a channel region between the source and drain regions in a semiconductor surface layer formed on an underlying insulating portion, and an electrically interconnected gate formed of a silicon carbide [material] compound  $Si_{1,r}C_r$ , wherein x is less than 0.5, the gate being connected to receive an input signal.

[Twice Amended] An integrated circuit device comprising: 11.

a substrate;

a p-channel transistor formed in a first portion of the substrate, the p-channel transistor including a source region, a drain region, a channel region between the source and drain regions, and an electrically interconnected silicon carbide gate over the channel region and separated therefrom by an insulating layer, the gate of the p-channel transistor comprising a silicon carbide compound  $Si_1, C_n$ , wherein x is less than 0.5, and being connected to receive a first input signal; and

an n-channel transistor formed in a second portion of the substrate, the n-channel transistor including a source region, a drain region, a channel region between the source and drain regions, and an electrically interconnected silicon carbide gate over the channel region and separated therefrom by an insulating layer, the gate of the n-channel transistor comprising a

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